

[Document Name] Abstract

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[Task] To provide a monomer that can become a raw material of a base
polymer for resist materials and optical materials that are required to be low
5 in light scattering and absorption and to be high in transparency.

[Solving Means] A fluorine-containing allyl ether compound represented by
the following general formula 1.

[Chem. 1]



10 (In the formula, R represents an organic group containing at least one fluorine
atom and having an alicyclic structure.)

A fluorine-containing allyl ether of the present invention can be
copolymerized with monomers, such as α -trifluoromethyl acrylic esters and
acrylic esters, that are useful for resist resins.

15 [Selected Drawing] None